





IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

_	oplication of: ation No.:	Barstad et al. 09/605,442 June 28, 2000 ELECTROLYTIC COPPER	R PLATING S	Group No.: Examiner: SOLUTIONS	1741 W. Nicolas	
Comn P.O. E	Stop nissioner for Pa Box 1450 ndria, Virginia					
		AMENDMENT	TRANSMI	ITTAL		
1.	Transmitted he	erewith is an amendment fo	or this applic	eation.		
		STA	ATUS			
2.		l entity. han a small entity.				
		EXTENSIO	N OF TER	M		
NOTE:	Non-Final Office A	in Patent Cases (Supplement Amen action, an extension of time is not r he shortened statutory period.				
		CERTIFICATE OF MAILING/I	RANSMISSIC	ON (37 C.F.R. 1.8)	(a))	_
I hereby	certify that, on the d	ate shown below, this corresponder	nce is being:			
	MA	ILING		FAC	SIMILE	
[X]	with sufficient pos- envelope addressed	United States Postal Service tage as First Class Mail in an to the Commissioner for 1450, Alexandria, Virginia	[]	Trademark Office.	simile to the Patent and	
Date:	6/24/03	_		Peter F. Corless rint name of person	n certifying)	_

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(Amendment Transmittal—page 1 of 4)

If a timely response has been filed after a Final Office Action, an extension of time is required to permit filing and/or entry of a Notice of Appeal or filing and/or entry of an additional amendment after expiration of the shortened statutory period unless the timely-filed response placed the application in condition for allowance. Of course, if a Notice of Appeal has been filed within the shortened statutory period, the period has ceased to run." Notice of December 10, 1985 (1061 O.G. 34-35).

NOTE: See 37 C.F.R. 1.645 for extensions of time in interference proceedings, and 37 C.F.R. 1.550(c) for extensions of time in reexamination proceedings.

3. The proceedings herein are for a patent application and the provisions of 37 C.F.R. 1.136 apply.

(complete (a) or (b), as applicable)

(a) [X] Applicant petitions for an extension of time under 37 C.F.R. 1.136 (fees: 37 C.F.R. 1.17(a)(1)-(4)) for the total number of months checked below:

	Extension	Fee for other than	Fee for
	(months)	small entity	small entity
[]	one month	\$110.00	\$55.00
[X]	two months	\$410.00	\$205.00
[]	three months	\$930.00	\$465.00
[]	four months	\$1,450.00	\$725.00
[]	five months	\$1,970.00	\$985.00

Fee: \$ 410.00

If an additional extension of time is required, please consider this a petition therefor.

(check and complete the next item, if applicable)

overlooked the need for a petition for extension of time.

[]	An extension for months has already been secured. The fee paid therefor of \$ is deducted from the total fee due for the total months of extension now requested.							
		Extension fee due with this request \$_410.00						
		OR						
(b)	[]	Applicant believes that no extension of term is required. However, this conditional petition is being made to provide for the possibility that applicant has inadvertently						

FEE FOR CLAIMS

4. The fee for claims (37 C.F.R. 1.16(b)-(d)) has been calculated as shown below:

	(Col.1))	(Col.	2) (Col. 3) SM	IALL EN	ΓΙΤΥ			THAN A ENTITY	
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	Amen	dmer	nt	Paid For	Extra	Rate	Fee_	OR	Rate	Fee
Total		*	Minus	**	=	x \$9 =	\$0		x \$18 =	\$
Indep.		*	Minus	***	=	x \$42 =	\$0		x \$84 =	\$ 0
[] Fir	st Prese	ntatio	on of Mul	tiple Depender	nt Claim	+ \$140 =	\$0		+ \$280 =	\$ 0
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WARNING: "After final rejection or acc requirement of form which									g with any	
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	(c)	[X]	No a	dditional fee fo	or claims i	•				
	(d)	[]	Total	additional fee			•			
					FEE PAY	MENT				
5.	[X]	Atta	ched is a	check in the si	um of \$ _4	410.00				
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				F	EE DEFI	CIENCY				
NOTE:	IOTE: If there is a fee deficiency and there is no authorization to charge an account, additional fees are necessary to cover the additional time consumed in making up the original deficiency. If the maximum, six-month period has expired before the deficiency is noted and corrected, the application is held abandoned. In those instances where authorization to charge is included, processing delays are encountered in returning the papers to the PTO Finance Branch in order to apply these charges prior to action on the cases. Authorization to charge the deposit account for any fee deficiency should be checked. See the Notice of April 7, 1986, (1065 O.G. 31-33).						pired thorization h in order			
6.	[X]	If an	ny additio	nal extension a	nd/or fee i	is required, ch	arge Acc	ount N	o. <u>04-110</u>	5

AND/OR

[X]	If an	v additional	fee for clair	ns is required	l, charge Account No.	04-1105.
Δ	II ali	y auditionai	ice ioi cian	iis is required	i, charge Account No.	

SIGNATURE OF PRACTITIONER

Reg. No. 33,860

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(type or print name of practitioner)

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PATENT TRADEMARK OFFICE





Docket No. 50439-2

18/00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT:

Barstad et al.

SERIAL NO.:

09/605,442

EXAMINER: W. Nicholas

FILED:

June 28, 2000

GROUP:

1741

FOR:

PHOTOACID GENERATORS AND PHOTORESISTS

COMPRISING SAME

THE HONORABLE COMMISSIONER OF PATENTS AND TRADEMARKS WASHINGTON, DC 20231

SIR:

RESPONSE TO OFFICE ACTION

Applicants are in receipt of the Office Action dated January 24, 2003. Applicants respond to that Office Action as follows.

Claims 124-136 were rejected under 35 U.S.C. 102(e) over Landau et al. (U.S. Patent 6,379,522).

Claims 137-153 were rejected under 35 U.S.C. 103 over Landau et al. (U.S. Patent 6,379,522) and further in view of Dahms et al. (U.S. Patent 5,433,840).

For the sake of brevity, the two rejections are addressed in combination. Such a combined response is considered appropriate because, *inter alia*, both rejections rely on the Landau et al. document as a sole or primary citation.

As an initial matter, Applicants will submit under separate cover a Rule 131 Declaration which will antedate the Landau et al. citation and thereby obviate the rejections.

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The instant rejections are not sustainable for additional reasons.

Among other things, the proposed combination of Landau et al. and Dahms et al. is not proper for purposes of a Section 103 rejection.

For instance, the Landau et al. document is specifically directed to a low-acid system and *teaches away* from use of higher acid concentrations. Thus, for example, Landau et al. states the following at column 4, lines 5 (bold emphasis added):

The conventional copper plating electrolyte includes a relatively high sulfuric acid concentration (from about 45 g of H₂SO₄ per l. of H₂O (0.45M) to about 110 g/l. (1.12M) which is provided to the solution to provide high conductivity to the electrolyte. The high conductivity is necessary to reduce the non-uniformity in the deposit thickness caused by the cell configuration and the differently shaped parts encountered in conventional electroplating cells. However, the present invention is directed primarily towards applications where the cell configuration has been specifically designed to provide a relatively uniform deposit thickness distribution on given parts. However, the substrate is resistive and imparts thickness non-uniformity to the deposited layer. Thus, among causes of non-uniform plating, the resistive substrate effect may dominate and a highly conductive electrolyte, containing, e.g., high H₂SO₄ concentrations, is unnecessary. In fact, a highly conductive electrolyte (e.g., generated by a high sulfuric acid concentration) is detrimental to uniform plating because the resistive substrate effects are amplified by a highly conductive electrolyte.

* * * *

Also, a lower supporting electrolyte concentration (e.g., sulfuric acid concentration in copper plating) often permits the use of a higher metal ion (e.g., copper sulfate) concentration due to elimination of the common ion effect as explained above. Furthermore, in systems where a soluble copper anode is used, a lower added acid concentration (or preferably no added acid at all) minimizes harmful corrosion and material stability problems.

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In clear distinction, the Dahms et al. document reports use of *high acid* concentrations. See Dahms et al. at column 4, lines 5-8 and the examples.

Thus, the skilled worker would have had no incentive to carefully select a component of the high-acid content composition of Dahms et al. and insert that selected component into the low-acid or no-acid composition of the system reported by Landau et al., as has been proposed by the instant rejection. See Section 2143.01 of the Manual of Patent Examining Procedure.

For such reasons, reconsideration and withdrawal of the rejections are requested.

Respectfully submitted,

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